

PTW ASIA PTE LTD

FEI Helios 400			
Manufacturer	FEI		
Model	Helios 400	Helios 400	
Description	Dual Beam	Dual Beam	
Serial Number	D5031	D5031	
Year of Manufacture	2007 (updated 20	2007 (updated 2010)	
Speifications			
Beam	Electron	Elestar: 0.35kV-30kV	
	lon	Sidewinder: 0.5kV-30kV	
Resolution	Electron	up to 1nm at 5kV	
	lon	Up to 4.5 nm @ 30kV	
Stage	size	100x100 mm	
	Tilt	-10 to +60 Degree	
	visual size	80 mm Diameter	
	Piezo Stage	With Load Lock	
Detectors	ETD,CDM,TLD		
GIS	Max 4	Installed: Idep, PT, EE	
Additional Possible	 Evactron 10 Plasma Cleaner anti Vibration platform Faraday Cage, around the machine, including the magnetic compensator. 		







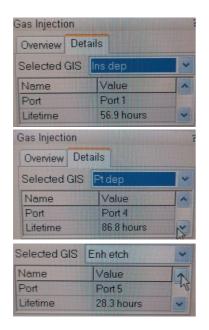


Made in the Netherlan	ds CE
Type: PW 2046/34	230 V ~
NC :9432 020 46341	50/60 Hz
S/N : D5031	10 A

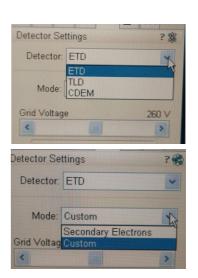
Explorin	g New Dimensions
xTm Copyright @) FEI Company 1999 - 2010
Uses XJ Charts	XJ Technologies
Product Version	3.8.8.1937
Build Date	07-01-2010
Build Number	1937 [Release]
DNumber	D5031
Machine Type	Helios NanoLab 400



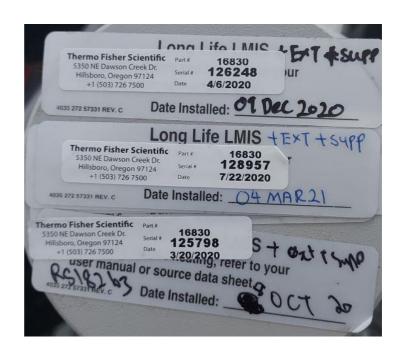


















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All Equipment is offered subject to prior sale. This item will be quoted based upon specific terms and configuration required. Interested parties may contact PTW Asia Pte Ltd at: ask@ptwsingapore.com

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